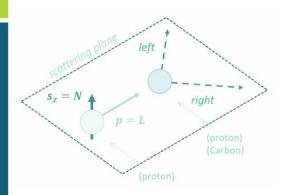


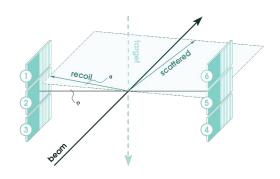
# Simulations of hadron polarimetry: impact of second layer of silicon detectors

Ana S. Nunes BNL/EIC Weekly Meeting September 27<sup>th</sup>, 2021



## Hadron polarimetry: method and data



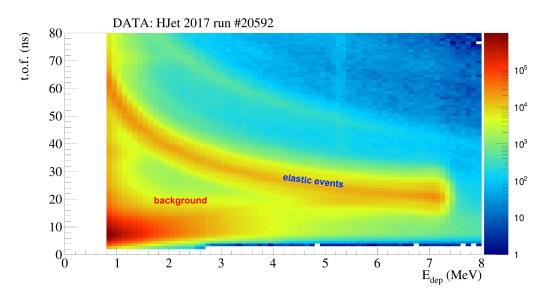


#### **Basis:**

#### **Elastic scattering in CNI-region**

-> left-right asymmetry of recoil particles:  $\epsilon = \frac{N_L - N_R}{N_L + N_R}$ 

Asymmetry and polarization are related through analyzing power:  $\epsilon = A_N P$ 



### Introduction to the HJet

Hadron polarimetry method at the HJet: based on elastic scattering pp->pp events (in the CNI interference region), selected based on t.o.f., E<sub>dep</sub> and angle of recoil particle

#### To be understood:

Sources of background

Conditions of tests

#### **Used in MC simulations:**

**Pythia6**, "minimum bias" processes (11, 12, 13, 28, 53, 68, 91, 92, 93, 94, 95), E<sub>beam</sub> = 255 GeV, 1B events

**HjetSim** (by Oleg Eyser), based on Geant4, with:

HJet width  $\sigma$ =26 mm

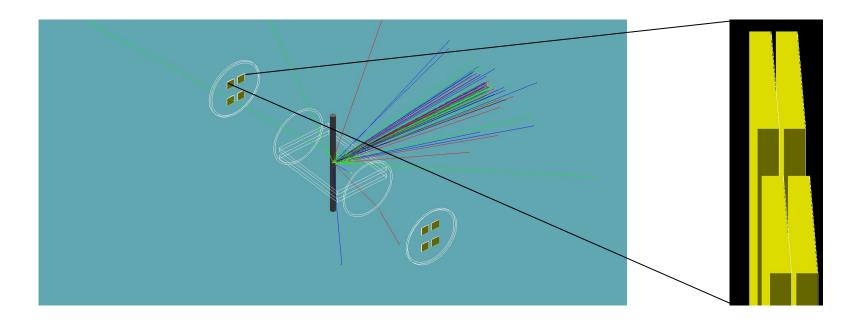
Beam bunches longitudinal extension  $\sigma$ =3.5 ns

Surrounding material: flanges behind the detectors, cylindrical detector chambers, "target chamber"

- \* 2 layers of silicon detectors, w/ dead layers
- \* W/o and w/ ceramic layer (1.6 mm of alumina)

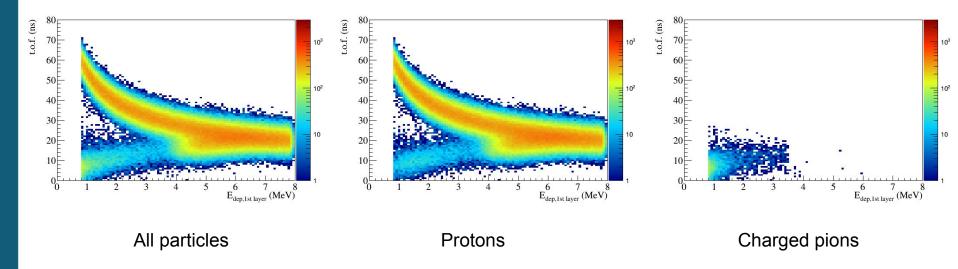


## **HJet: setup for simulations**





## Simulation results: t.o.f. vs $E_{dep}$

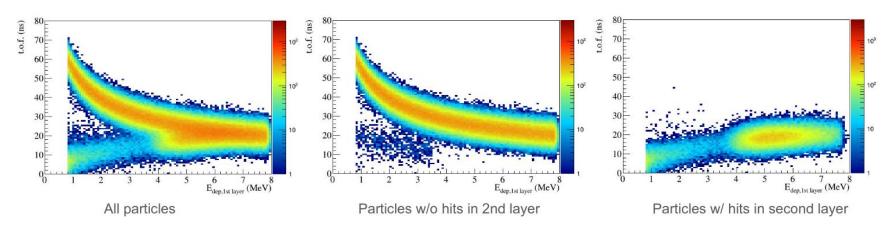


 Punch-through protons and charged pions are identified as sources of background to the elastic event selection



## Using second Si layer to veto background

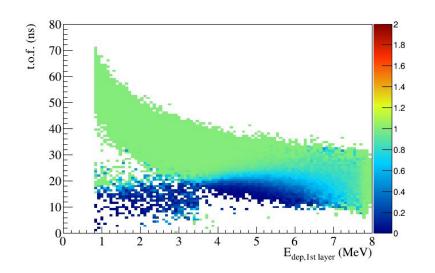
Without ceramic layer

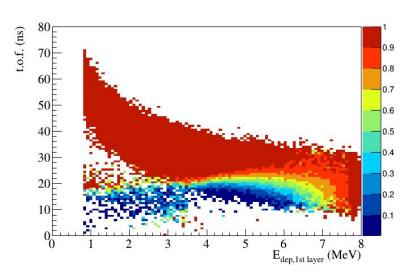


 Vetoing particles that reach the second Si layer allows to clean the sample to be used for the polarimetry measurement, by removing both punch-through protons and low t.o.f. and low E<sub>dep</sub> particles (charged pions)



## Fraction of particles surviving after veto



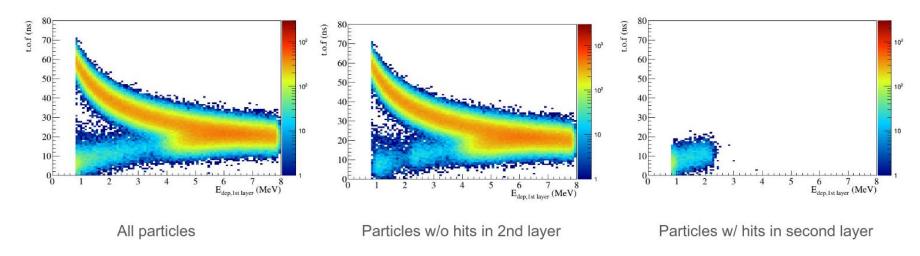


 Vetoing particles that reach the second Si layer allows to clean the sample to be used for the polarimetry measurement, by removing both punch-through protons and low t.o.f. and low E<sub>dep</sub> particles (charged pions)



## Including a ceramic layer in between Si

With ceramic layer, 1.6 mm thickness



The presence of a ceramic layer, as was used in previous tests, limits the particles that reach
the second layer of Si, thereby limiting the effectiveness of its use for sample cleanup



### Introduction to the pC polarimeters

<u>Hadron polarimetry method at the pC polarimeters:</u> based on elastic scattering pC->pC events (in the CNI interference region), selected based on t.o.f. and  $E_{dep}$  of recoil particle

#### To be understood:

Sources of background

Conditions of tests

#### **Used in MC simulations:**

**Dpmjet3**, "minimum bias" processes except elastic scattering,  $E_{\text{beam}}$  = 255 GeV, 1M events

Adapted **HjetSim** (by Oleg Eyser), based on Geant4, with:

Thin carbon ribbon as target

Beam bunches longitudinal extension  $\sigma$ =3.5 ns

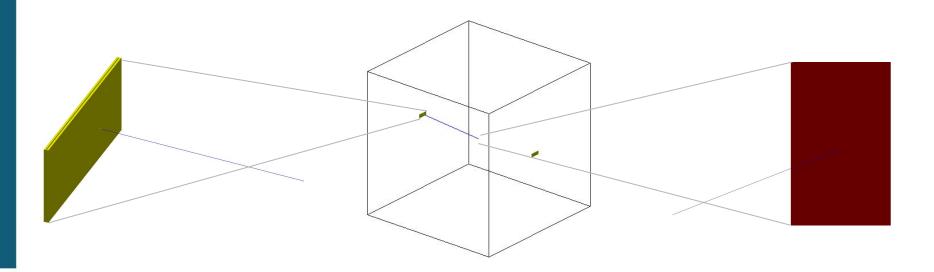
Surrounding material

\* 2 layers of silicon detectors

Also thanks to Jaroslav Adam who adapted hepevt class to also read nuclei

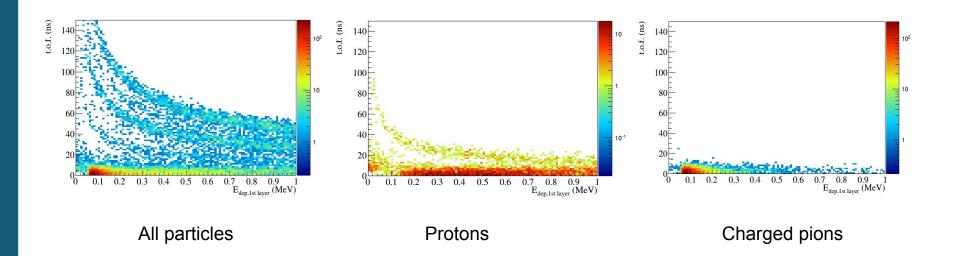


# pC polarimeters: (simplified) setup used for simulations





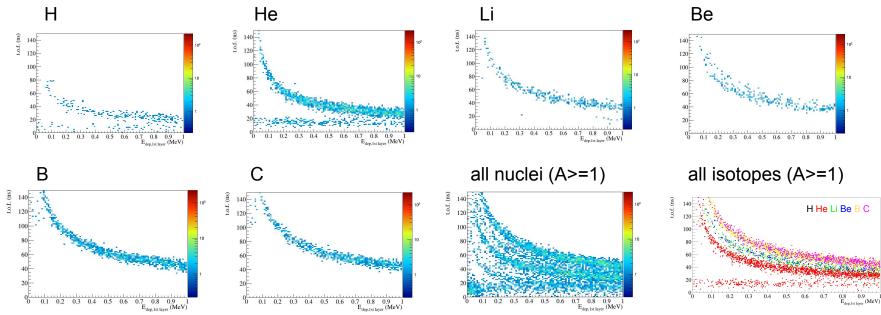
## Simulation results: t.o.f. vs $E_{dep}$





## Simulation results: t.o.f. vs E<sub>dep</sub>

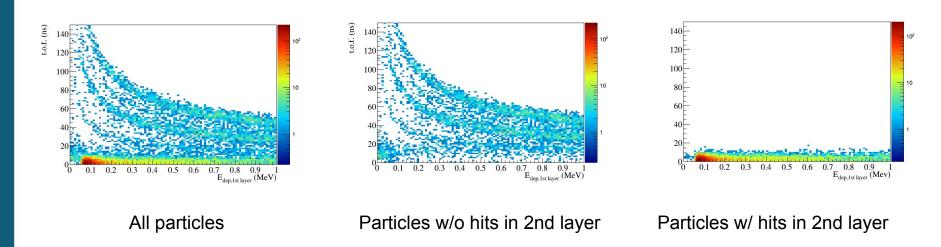
Generator: Dpmjet3 (not including elastic scattering; simulating the background to the elastic pC→pC events)





## pC polarimeters: impact of Si second layer

Generator: Dpmjet3 (not including elastic scattering; simulating the background to the elastic pC→pC events)



The second layer of silicon allows to veto particles of very low t.o.f.



## Summary

#### For the HJet:

The background at low t.o.f. and low  $E_{\rm dep}$  is composed of charged pions

A second layer of Si detectors can in principle be used to veto punch-though protons and background charged pions

The presence of a ceramic layer reduced the effectiveness of the veto

#### For pC polarimeters:

A double layer of silicon can veto particles only at very low t.o.f., below ~10 ns



## **Backup**



### **HJet Simulation**

#### Event generator: Pythia 6, "minimum bias" process mix

```
\begin{aligned} &11: f_i f_j \to f_i f_j \\ &12: f_i f_i \to f_k f_k \\ &13: f_i \bar{f}_i \to f_k \bar{f}_k \\ &28: f_i g \to f_i g \\ &53: gg \to f_k \bar{f}_k \\ &68: gg \to gg \\ &91: \text{elastic scattering} \end{aligned}
```

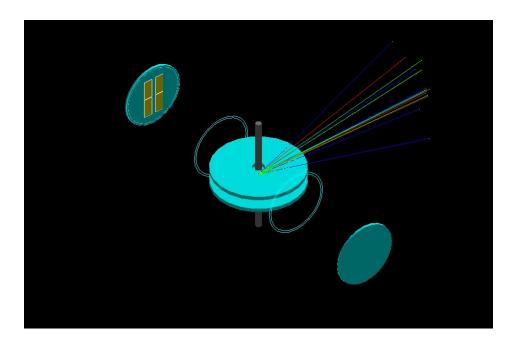
92 : single scattering  $(AB \to XB)$ 93 : single scattering  $(AB \to XA)$ 

94 : double diffraction 95 : low  $p_{\perp}$  production

$$E_{beam} = 255 \text{ GeV}$$

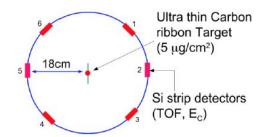


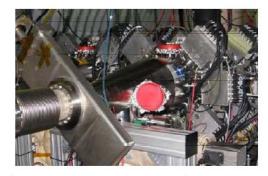
Passage through matter: Geant 4 (HJetSim, by Oleg Eyser)



#### **Local Hadron Polarimetry**

- Measurement of the polarization vector at the interaction point (IP-6)
  - Inside spin rotators and crab cavities
  - Ensure longitudinal polarization orientation
- Non-destructive with minimal impact on beam lifetime
- Rapid, quasi-online analysis for fast feedback during accelerator setup
- Elastic recoil from ultra-thin Carbon target
- Silicon strip detectors
  - Measure energy and time-of-flight
- Move part of the setup from RHIC IP-12 to EIC IP-6
  - Vacuum chamber, target station, detector chambers
- Modify detector setup for improved inelastic background rejection
- Modify readout for reduced bunch spacing
- Identify adequate target material for EIC conditions
  - Target heating from beam







Bill Schmidke Oleg Eyser

